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PTO-1449 (Modified)  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 213.002-D1-US	SERIAL NUMBER 10/646,313
	APPLICANT(S) Ye et al.	
	FILING DATE August 22, 2003	GROUP ART UNIT 2878

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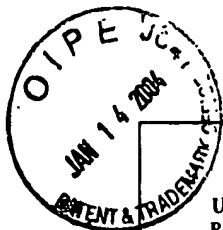
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1	"Aerial Image Measurements on a Commercial Stepper", Fields, et al., SPIE Vol. 2197, 1994, pp.585-595
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1	"Improving Photomask Linewidth Measurement Accuracy via Emulated Stepper Aerial Image Measurement", J. Potzick, SPIE Vol. 2322, Photomask Technology and Management, 1994, pp.353-359
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1	"Meeting the Challenge of Advanced Lithography Reticle Inspection", Zurbrick et al., SPIE Vol. 2322, Photomask Technology and Management, 1994, pp.7-15
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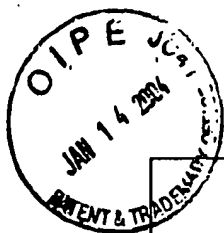
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l	"Application of the Aerial Image Measurement System (AIMS™) to the Analysis of Binary Mask Imaging and Resolution Enhancement Techniques", Martino et al., SPIE Vol. 2197, 1994, pp.573-584
l	"Optical Limitations to Cell Size Reduction in IT-CCD Image Sensors", Satoh et al., IEEE, Transactions on Electron Devices, Vol. 44, No. 10, Oct. 1997, pp.1599-1603
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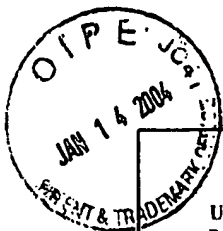
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